Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1 - 11 (canceled)

12. (currently amended) A vacuum processing apparatus installed in a floor in a building comprising:

a transfer box inside of which an object wafer to be processed is transferred under an atmospheric condition by a transfer robot disposed therein, the transfer box enabling holding of a plurality of wafer cassettes installed at a front side portion thereof;

a vacuum transfer unit disposed at a back side portion of the transfer box and detachably coupled to a back side surface portion of the transfer box, the vacuum transfer unit enabling transfer of the object wafer therein under a vacuum condition;

at least one <u>of a plurality of vacuum processing chamber-chambers being</u>
disposed at a back or lateral side of the vacuum transfer unit and being detachably
connected thereto, the at least one <u>of the plurality of vacuum processing chamber</u>
<u>chambers</u> being supplied with gas and enabling processing of the object wafer
transferred under the vacuum condition by a plasma generated therein; and

a plurality of connector portions of utility paths which connect with paths

arranged in from another floor of [[a]] the building different from [[a]] the floor of the building in which the vacuum processing apparatus is installed so that the at least one vacuum processing chamber is disposed above the floor, the plurality of

connector portions of the utility paths being disposed so as to extend substantially linearly above the floor of the building and under a connecting portion of the [[the]] vacuum transfer unit[[, and]] from the back side surface portion of the transfer box and along the back side surface;

wherein the utility paths enable supply of utilities including the gas supplied from the building having the vacuum processing apparatus installed therein to the vacuum transfer unit or the at least one of the plurality of vacuum processing chamber chambers and enables discharge of exhaust from the vacuum transfer unit or the at least one of the plurality of vacuum processing chamber chambers including the utilities supplied thereto.

13. (currently amended) A vacuum processing apparatus <u>installed in a floor of a</u> building comprising:

an atmospheric block including a transfer box inside of which an object wafer to be processed is transferred under an atmospheric condition by a transfer robot disposed therein, the transfer box enabling holding of a plurality of wafer cassettes installed at a front side surface portion thereof;

a vacuum transfer unit disposed at a back side of a back side surface portion of the transfer box and detachably connected thereto by a connection portion thereof, the vacuum transfer unit enabling transfer of the object wafer therein under a vacuum condition;

a vacuum processing block, installed at a connecting portion [[of]] between the vacuum transfer unit and the transfer box;

a plurality of vacuum processing chambers of the vacuum processing block being disposed at a back or lateral side of the vacuum transfer unit and being detachably connected thereto, at least one of the plurality of vacuum processing chambers being supplied with gas and enabling processing of the object wafer transferred under the vacuum condition by a plasma generated therein, the vacuum processing block comprising the vacuum transfer unit and the plurality of vacuum processing chambers; and

a plurality of connector portions of utility paths which connect with paths arranged in from another floor of [[a]] the building different from [[a]] the floor of the building in which the vacuum processing apparatus is installed—so that the plurality of vacuum processing chambers are disposed above the floor, the plurality of connector portions of the utility paths being disposed so as to extend substantially linearly above the floor of the building and under [[a]] the connecting portion [[of]] between the transfer box and the vacuum transfer unit[[, and]] along from the back side surface portion of the transfer box—in the back side thereof;

wherein the utility paths enables supply of utilities including the gas supplied from [[a]] the building having the vacuum processing apparatus installed therein to the vacuum transfer unit or the at least one of the <u>plurality of vacuum processing</u> chambers and enable discharge of exhaust from the vacuum transfer unit or the at least one of the <u>plurality of vacuum processing</u> chambers including the utilities supplied thereto.

- 14. (previously presented) The vacuum processing apparatus according to claim 12, wherein the utilities include plural kinds of gases, water and air supplied from the building.
- 15. (canceled)
- 16. (canceled)
- 17. (previously presented) The vacuum processing apparatus according to claim 14, wherein the connector portions of the utility paths are disposed under at least one

load lock chamber consisting of the connection portion between the transfer box and the vacuum transfer unit.

- 18. (previously presented) The vacuum processing apparatus according to claim 14, further comprising display units disposed at the back side surface portion of the transfer box and enable display of a status of the utility.
- 19. (previously presented) The vacuum processing apparatus according to claim 13, wherein the utilities include plural kinds of gases, water and air supplied from the building.
- 20. (canceled)
- 21. (canceled)
- 22. (previously presented) The vacuum processing apparatus according to claim 19, wherein the connector portions of the utility paths are disposed under at least one load lock chamber consisting of the connection portion between the transfer box and the vacuum transfer unit.
- 23. (previously presented) The vacuum processing apparatus according to claim 13, further comprising display units disposed at the back side surface portion of the transfer box and enable display of a status of the utility.